

Abstract Submitted
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Aluminum Nanowire Arrays via Soft Nanoimprint Lithography¹

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²N. T. Nesbitt, J. M. Merlo, A. H. Rose, Y. M. Calm, K. Kempa, M. J. Burns, & M. J. Naughton, *Nano Lett.* **15**, 7294-7299 (2015)

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